	Application No.	Applicant(s)	
Notice of Allowability	10/051,906	SU ET AL.	
	Examiner	Art Unit	
	John Ruggles	1756	
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in this apport or other appropriate communication (GHTS. This application is subject to	plication. If not included will be mailed in due of	l ourse. THIS
1. This communication is responsive to the submissions filed	<u>on 5/13/05</u> .		
2. X The allowed claim(s) is/are 1-4,8,10-19 and 21-24.		•	
3. \boxtimes The drawings filed on <u>13 May 2005</u> are accepted by the Ex	kaminer.		
4. ☐ Acknowledgment is made of a claim for foreign priority un a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. ☐ A SUBSTITUTE OATH OR DECLARATION must be subminsformal PATENT APPLICATION (PTO-152) which give 6. ☐ CORRECTED DRAWINGS (as "replacement sheets") must (a) ☐ including changes required by the Notice of Draftspers 1) ☐ hereto or 2) ☐ to Paper No./Mail Date (b) ☐ including changes required by the attached Examiner's Paper No./Mail Date identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in tild 7. ☐ DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT in the composition of the comment regarding REQUIREMENT in the composition of the comment regarding REQUIREMENT in the comment regarding requirement sheet in the comment regarding requirement regarding requirement sheet in the comment of the comment and the comment of the comment of the comment of the co	e been received. been received in Application No cuments have been received in this of this communication to file a reply IENT of this application. itted. Note the attached EXAMINER as reason(s) why the oath or declarate to be submitted. son's Patent Drawing Review (PTO- as Amendment / Comment or in the Comment of the drawing the header according to 37 CFR 1.121(const of BIOLOGICAL MATERIAL researce).	national stage application complying with the requirement of the front (not the bid).	rirements
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. Notice of Informal P 6. Interview Summary Paper No./Mail Dat 7. Examiner's Amendr 8. Examiner's Stateme 9. Other	(PTO-413), te ment/Comment	rance

Response to Amendment

The supplemental amendment #2 filed on 5/13/05 to correct Figure 3A has been entered.

Allowable Subject Matter

Claims 1-4, 8, 10-19, and 21-24 are allowed.

The following is an examiner's statement of reasons for allowance: Applicants' arguments filed on 5/13/05 have been fully considered and are now persuasive. The prior art does not clearly teach the claim 1 limitation of forming a temporary protective layer over a passivation layer and an exposed UBM layer, in which the protective layer comprises a resinous organic material (recited to comprise benzocyclobutene (BCB) in dependent claim 3) having a glass transition temperature (T_g) that is about greater than (defined at page 18 lines 3-4 to mean equal to or greater than) a solder reflow temperature for protecting a semiconductor process wafer surface from thermally degraded photoresist to improve a solder ball formation process. Therefore, claim 1 is allowable over the prior art and claims 2-4, 8, 10, and 21-22 are also allowable, due to their dependence on claim 1. Similarly, the prior art does not clearly teach the claim 11 limitation of forming a temporary protective layer overlying a semiconductor wafer process surface that comprises a UBM contact layer, in which the protective layer comprises a resinous organic material (recited to comprise benzocyclobutene (BCB) in dependent claim 13) having a glass transition temperature (T_g) that is greater than a solder column reflow temperature for forming a solder ball to avoid photoresist residue in a solder ball formation process. Therefore, claim 11 is allowable over the prior art and claims 12-19 and 23-24 are also allowable, due to their dependence on claim 11.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to John Ruggles whose telephone number is 571-272-1390. The examiner can normally be reached on Monday-Thursday and alternate Fridays.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

hn Ruggles

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SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 1700